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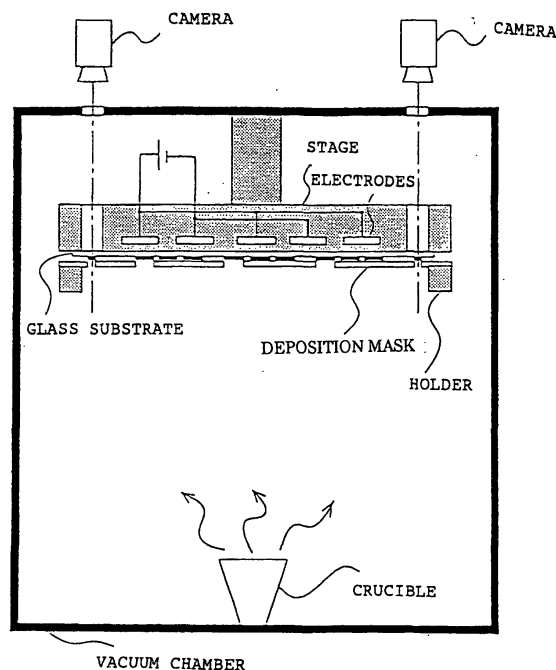
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(54) **Mask vapor deposition method and apparatus, mask, process for manufacturing display panel, display panel and electronic device**

(57) A method includes a step of attracting a glass substrate 20 that is a subject for deposition using the electrostatic attraction of a stage 1, a step of aligning the attracted glass substrate with a deposition mask 2, and a step of evaporating an organic compound that is

a deposition material, used for forming electroluminescent elements so as to deposit the compound on the glass substrate 20. An electrostatic chucking function is provided to the deposition mask according to needs, whereby the adhesion is enhanced.

FIG. 1





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The present search report has been drawn up for all claims			
Place of search The Hague		Date of completion of the search 10 June 2004	Examiner Ekhuft, H
CATEGORY OF CITED DOCUMENTS		T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document	
X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document			

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**ANNEX TO THE EUROPEAN SEARCH REPORT
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EP 03 02 7352

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For more details about this annex : see Official Journal of the European Patent Office, No. 12/82

专利名称(译)	掩模气相沉积方法和装置，掩模，制造显示面板的工艺，显示面板和电子器件		
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摘要(译)

一种方法包括使用台1的静电吸引吸引作为沉积对象的玻璃基板20的步骤，将吸引的玻璃基板与沉积掩模2对准的步骤，以及蒸发有机化合物的步骤。沉积材料，用于形成电致发光元件，以便将化合物沉积在玻璃基板20上。根据需要向沉积掩模提供静电吸附功能，从而增强粘附性。

FIG. 1

